

**PATENT****IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:

CHRISTIAN ZISTL, ET AL.

Group Art Unit: 2814

Serial No.: 09/634,209

Examiner: H. Pham

Filed: AUGUST 9, 2000

Atty. Dkt. No.: 2000.046600

For: IMPROVED DEPTH OF FOCUS (DOF)  
FOR TRENCH-FIRST-VIA-LAST (TFVL)  
DAMASCENE PROCESSING WITH  
HARD MASK AND LOW VISCOSITY  
PHOTORESIST

**DECLARATION UNDER 37 C.F.R. § 1.131 OF CHRISTIAN ZISTL**

1. My name is Christian Zistl. I have personal knowledge of the facts stated herein.

2. I am currently employed with Advanced Micro Devices-Saxony, a wholly-owned subsidiary of Advanced Micro Devices, Inc., in Dresden, Germany. I am a named inventor on application Serial No. 09/634,209 entitled "Improved Depth of Focus for Trench-First-Via-Last Damascene Processing with Hard Mask and Low Viscosity Photoresist."

3. Attached as Exhibit A is a copy of the invention disclosure form I prepared in Austin, Texas for the invention described in the above-referenced patent application. I prepared and signed the invention disclosure form on October 20, 1999, as indicated by the date adjacent my signature.

4. The attached invention disclosure form was provided with internal tracking number TT3851 by AMD's legal department, and it was sent to the law firm of Williams, Morgan & Amerson on or about January 13, 2000, with a request to prepare a United States patent application for the invention disclosed in the invention form.

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5. I understand that willful false statements and the like so made are punishable by fine or imprisonment, or both, and may jeopardize the validity of the application or any patent issuing thereon.

6. I declare under penalty of perjury that the foregoing is true and correct.

19. October 2004

Date



Christian Zistl

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